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said spacer being in electrical contact with one of said row-directed or column-directed wires.

1 58. An electron beam apparatus according to claim
1 57, wherein said plate-shaped spacer is rectangularly
parallelepiped in such a way that the longitudinal direction
thereof is in parallel with one of said row-directed or
column-directed wires with which said spacer is in electrical
contact.

1 59. An electron beam apparatus according to claim
1 57, wherein said row-directed wires are laminated over said
column-directed wires and said spacer is in electrical
contact with one of said row-directed wires, or wherein said
column-directed wires are laminated over said row-directed
wires and said spacer is in electrical contact with one of
said column-directed wires.

Bind

1 60. An electron beam apparatus according to claim
1 57, wherein said spacer has a semiconductor film on its
surface.

1 61. An electron beam apparatus according to claim
1 57, wherein said apparatus further comprises a target
arranged to be irradiated with an electron beam emitted from
said electron-emitting devices.